

THIS SHEET HAS BEEN
REPLACED

ABSTRACT

A process for producing a polishing composition,
which comprises preliminarily adjusting water to pH 2-4,
adding from 40 to 60 wt% of fumed silica to the water
5 under high shearing force, adding water to lower the
viscosity to 2-10000 cps, stirring the mixture under low
shearing force for at least 5 minutes, adding water to
lower the fumed silica concentration to 10-38 wt%, and
adding a basic substance under vigorous stirring to raise
10 the pH to 9-12.

This Sheet Has Been Replaced

